

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION

(PTO-1449)



ATTY. DOCKET NO.
005916
USA/FPS/MMCS/MC

SERIAL NO.
09/998,384

APPLICANT
Young Joseph PAIK

FILING DATE
November 30, 2001

GROUP
2812 2823

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
K.N.	4,901,218	02/13/90	Cornwell			03/04/88
	5,427,878	06/27/95	Corliss			05/16/94
	5,761,065	06/02/98	Kittler et al.			03/30/95
	5,862,054	01/19/99	Li			02/20/97
	5,912,678	06/15/99	Saxena et al.			04/14/97
	5,926,690	07/20/99	Toprac et al.			05/28/97
	6,074,443	06/13/00	Venkatesh et al.			01/29/98
	6,111,634	08/29/00	Pecen et al.			05/28/97
	6,150,664	11/21/00	Su			06/29/99
	6,245,581 B1	06/12/01	Bonser et al.			04/19/00
	2001/0044667 A1	11/22/01	Nakano et al.			05/16/01
	6,346,426 B1	02/12/02	Toprac et al.			11/17/00
	6,363,294 B1	03/26/02	Coronel et al.			12/29/98
	6,442,496 B1	08/27/02	Pasadyn et al.			08/08/00
	6,486,492 B1	11/26/02	Su			11/20/00
	6,492,281 B1	12/10/02	Song et al.			09/22/00
	6,540,591 B1	04/01/03	Pasadyn et al.			04/18/01
	6,560,504 B1	05/06/03	Goodwin et al.			09/29/99
	6,590,179 B2	07/08/03	Tanaka et al.			02/26/01
	6,604,012 B1	08/05/03	Cho et al.			08/23/00
	6,618,692 B2	09/09/03	Takahashi et al.			02/26/01
✓	6,625,497 B2	09/23/03	Fairbairn et al.			07/10/01
K.N.	6,640,151 B1	10/28/03	Somekh et al.			12/22/99

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DATE CONSIDERED

08/20/04

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FOREIGN PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation
						Yes
K.N.	0 397 924 A1	11/22/90	Europe			X

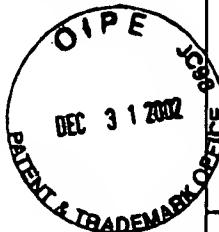
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)	
K.N.	Rocha, Joao and Carlos Ramos. September 12, 1994. "Task Planning for Flexible and Agile Manufacturing Systems." <i>Intelligent Robots and Systems '94. Advanced Robotic Systems and the Real World, IROS '94. Proceedings of the IEEE/RSJ/GI International Conference on Munich, Germany 12-16 Sept. 1994</i> . New York, New York: IEEE. pp. 105-112.
✓	March 15, 2002. Office Action for U.S. Serial No. 09/469,227, filed December 22, 1999.
✓	March 29, 2002. Office Action for U.S. Serial No. 09/363,966, filed July 29, 1999.
✓	June 20, 2002. Office Action for U.S. Serial No. 09/619,044, filed July 19, 2000.
✓	September 26, 2002. Office Action for U.S. Serial No. 09/637,620, filed August 11, 2000.
✓	October 23, 2002. Office Action for U.S. Serial No. 09/469,227, filed December 22, 1999.
✓	December 17, 2002. Office Action for U.S. Serial No. 09/363,966, filed July 29, 1999.
✓	February 10, 2003. Office Action for U.S. Serial No. 09/619,044, filed July 19, 2000.
✓	April 9, 2003. Office Action for U.S. Serial No. 09/928,474, filed August 14, 2001.
✓	May 8, 2003. Office Action for U.S. Serial No. 09/637,620, filed August 11, 2000.
✓	June 18, 2003. Office Action for U.S. Serial No. 09/655,542, filed September 6, 2000.
✓	August 8, 2003. International Search Report for PCT/US03/08513.
✓	August 25, 2003. Office Action for U.S. Serial No. 10/100,184, filed March 19, 2002.
✓	September 15, 2003. Office Action for U.S. Serial No. 09/928,474, filed August 14, 2001.
✓	November 5, 2003. Office Action for U.S. Serial No. 10/172,977, filed June 18, 2002.
✓	December 1, 2003. Office Action for U.S. Serial No. 10/173,108, filed June 18, 2002.
✓	December 11, 2003. Office Action for U.S. Serial No. 09/943,383, filed August 31, 2001.
✓	December 16, 2003. International Search Report for PCT/US03/23964.
✓	January 20, 2004. Office Action for U.S. Serial No. 09/927,444, filed August 13, 2001.
✓	January 23, 2004. International Search Report for PCT/US02/24860.
K.N.	February 2, 2004. Office Action for U.S. Serial No. 09/363,966, filed July 29, 1999.

EXAMINER <i>J. K. Hwang, Lawyer</i>	DATE CONSIDERED 08/20/04
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EXAMINER'S INITIALS	PUBLICATION / PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
K.N.	5,270,222	12/14/93	Moslehi			12/31/90
K.N.	5,375,064	12/20/94	Bollinger			12/02/93
K.N.	5,599,423	02/04/97	Parker et al.			06/30/95
K.N.	5,844,554	12/01/98	Geller et al.			09/17/96

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PUBLICATION / PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	WO 95/34866	12/21/95	WO			X	
	WO 98/45090	10/15/98	WO			X	
	EP 0 881 040 A2	12/02/98	Europe			X	
	WO 99/25520	05/27/99	WO			X	
	WO 00/54325	09/14/00	WO			X	
K.N.	EP 1 066 925 A2	01/10/01	Europe			X	
K.N.	EP 1 092 505 A2	04/18/01	Europe			X	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

K.N.	Hu, Albert, Kevin Nguyen, Steve Wong, Xiuhua Zhang, Emanuel Sachs, and Peter Renteln. 1993. "Concurrent Deployment of Run by Run Controller Using SCC Framework." IEEE/SEMI International Semiconductor Manufacturing Science Symposium. pp. 126-132.
	Hu, Albert, He Du, Steve Wong, Peter Renteln, and Emanuel Sachs. 1994. "Application of Run by Run Controller to the Chemical-Mechanical Planarization Process." IEEE/CPMT International Electronics Manufacturing Technology Symposium. pp. 371-378.
	Smith, Taber, Duane Boning, James Moyne, Arnon Hurwitz, and John Curry. June 1996. "Compensating for CMP Pad Wear Using Run by Run Feedback Control." Proceedings of the Thirteenth International VLSI Multilevel Interconnection Conference. pp. 437-439.
	Suzuki, Junichi and Yoshikazu Yamamoto. 1998. "Toward the Interoperable Software Design Models: Quartet of UML, XML, DOM and CORBA." Proceedings IEEE International Software Engineering Standards Symposium. pp. 1-10.
K.N.	Klein, Bruce. June 1999. "Application Development: XML Makes Object Models More Useful." Informationweek. pp. 1A-6A.

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U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PUBLICATION / PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
K.N.	5,889,991	03/30/99	Consolatti et al.			12/06/96
	6,183,345 B1	02/06/01	Kamono et al.			03/20/98
↓	6,253,366 B1	06/26/01	Mutschler, III			03/31/99
K.N.	6,298,470 B1	10/02/01	Breiner et al.			04/15/99

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PUBLICATION / PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	WO 01/52055 A3	07/19/01	WO			X	
↓	WO 01/57823 A2	08/09/01	WO			X	
	EP 1 182 526 A2	02/27/02	Europe			X	
↓	WO 02/17150 A1	02/28/02	WO			X	
K.N.	WO 02/33737 A2	04/25/02	WO			X	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

K.N.	Chemali, Chadi El, James Moyne, Kareemullah Khan, Rock Nadeau, Paul Smith, John Colt, Jonathan Chapple-Sokol, and Tarun Parikh. July/August 2000. "Multizone Uniformity Control of a Chemical Mechanical Polishing Process Utilizing a Pre- and Postmeasurement Strategy." J. Vac. Sci. Technol. A, Vol. 18(4). pp. 1287-1296. American Vacuum Society.
K.N.	Jensen, Alan, Peter Renteln, Stephen Jew, Chris Raeder, and Patrick Cheung. June 2001. "Empirical-Based Modeling for Control of CMP Removal Uniformity." Solid State Technology, Vol. 44, No. 6, pp. 101-102, 104, 106. Cowan Publ. Corp.: Washington, D.C.
K.N.	Sarfaty, Moshe, Arulkumar Shanmugasundram, Alexander Schwarm, Joseph Paik, Jimin Zhang, Rong Pan, Martin J. Seamons, Howard Li, Raymond Hung, and Suketu Parikh. April/May 2002. "Advance Process Control Solutions for Semiconductor Manufacturing." IEEE/SEMI Advanced Semiconductor Manufacturing Conference. pp. 101-106.
K.N.	October 4, 2002. International Search Report from PCT/US01/22833.
K.N.	October 23, 2002. International Search Report from PCT/US01/27406.
K.N.	November 7, 2002. International Search Report from PCT/US02/19061.
K.N.	November 11, 2002. International Search Report from PCT/US02/19117.
K.N.	November 12, 2002. International Search Report from PCT/US02/19063.

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U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
K.N.	4,796,194	01/03/89	Atherton			08/20/86
	5,089,970	02/18/92	Lee et al.			10/05/89
	5,108,570	04/28/92	Wang			03/30/90
	5,220,517	06/15/93	Sierk et al.			08/31/90
	5,236,868	08/17/93	Nulman			04/20/90
	5,260,868	11/09/93	Gupta et al.			10/15/91
	5,295,242	03/15/94	Mashruwala et al.			11/02/90
	5,309,221	05/03/94	Fischer et al.			12/31/91
	5,329,463	07/12/94	Sierk et al.			01/13/93
	5,367,624	11/22/94	Cooper			06/11/93
	5,398,336	03/14/95	Tantry et al.			06/16/93
	5,402,367	03/28/95	Sullivan et al.			07/19/93
	5,408,405	04/18/95	Mozumder et al.			09/20/93
K.N.	5,410,473	04/25/95	Kaneko et al.			12/16/92

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	01-283934	11/15/89	Japan			X	
K.N.	2,050,247	08/29/91	Canada			X	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

K.N.	Dishon, G., D. Eylon, M. Finarov, and A. Shulman. "Dielectric CMP Advanced Process Control Based on Integrated Monitoring." Ltd. Rehoveth, Israel: Nova Measuring Instruments.
K.N.	Runyan, W. R., and K. E. Bean. 1990. "Semiconductor Integrated Circuit Processing Technology." pg. 48. Reading, Massachusetts: Addison-Wesley Publishing Company.

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EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
K.N.	5,490,097	02/06/96	Swenson et al.			08/06/93
	5,495,417	02/27/96	Fuduka et al.			03/16/93
	5,497,316	03/05/96	Sierk et al.			04/04/95
	5,503,707	04/02/96	Maung et al.			09/22/93
	5,508,947	04/16/96	Sierk et al.			05/13/94
	5,629,216	05/13/97	Wijaranakula et al.			02/27/96
	5,657,254	08/12/97	Sierk et al.			04/15/96
	5,661,669	08/26/97	Mozumder et al.			06/07/95
	5,694,325	12/02/97	Fukuda et al.			11/22/95
	5,698,989	12/16/97	Nulman			09/13/96
	5,719,495	02/17/98	Moslehi			06/05/96
	5,740,429	04/14/98	Wang et al.			07/07/95
	5,751,582	05/12/98	Saxena et al.			09/24/96
	5,754,297	05/19/98	Nulman			04/14/97
K.N.	5,764,543	06/09/98	Kennedy			06/16/95

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	2,165,847	08/29/91	Canada			X	
K.N.	2,194,855	08/29/91	Canada			X	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

K.N.	Zorich, Robert. 1991. <i>Handbook of Quality Integrated Circuit Manufacturing</i> . pp. 464-498 San Diego, California: Academic Press, Inc.
K.N.	Rampalli, Prasad, Arakere Ramesh, and Nimish Shah. 1991. <i>CEPT—A Computer-Aided Manufacturing Application for Managing Equipment Reliability and Availability in the Semiconductor Industry</i> . New York, New York: IEEE.

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18/09/04

08/20/04

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APPLICANT Young Joseph PAIK			
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**U.S. PATENT DOCUMENTS**

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
K.N.	5,808,303	09/15/98	Schlagheck et al.			01/29/97
	5,838,595	11/17/98	Sullivan et al.			11/25/96
	5,883,437	03/16/99	Maruyama et al.			12/28/95
	5,910,011	06/08/99	Cruse			05/12/97
K.N.	6,054,379	04/25/00	Yau et al.			02/11/98

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	05-151231	06/18/93	Japan				X
	05-216896	08/27/93	Japan				X
	05-266029	10/15/93	Japan				X
	06-110894	04/22/94	Japan				X
	06-176994	06/24/94	Japan				X
	06-252236	09/09/94	Japan				X
	06-260380	09/16/94	Japan				X
	08-149583	06/07/96	Japan			X	
	09-34535	02/07/97	Japan			X	
	EP 0877308 A2	11/11/98	Europe			X	
	11-67853	03/09/99	Japan			X	
K.N.	1072967A3	11/21/01	Europe			X	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

K.N.	Moyne, James R., Nauman Chaudhry, and Roland Telfeyan. 1995. "Adaptive Extensions to a Multi-Branch Run-to-Run Controller for Plasma Etching." <i>Journal of Vacuum Science and Technology</i> . Ann Arbor, Michigan: University of Michigan Display Technology Manufacturing Center.
K.N.	Moyne, James, Roland Telfeyan, Arnon Hurwitz, and John Taylor. August 1995. "A Process-Independent Run-to-Run Controller and Its Application to Chemical-Mechanical Planarization." <i>SEMI/IEEE Advanced Semiconductor Manufacturing Conference and Workshop</i> . Ann Arbor, Michigan: The University of Michigan, Electrical Engineering & Computer Science Center for Display Technology & Manufacturing.

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U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT APPLICATION NO.	FILING DATE	NAME	TITLE	CLASS	SUB-CLASS
K.N.	09/363,966	07/29/99	Arackaparambil et al.	Computer Integrated Manufacturing Techniques		
K.N.	09/469,227	12/22/99	Somekh et al.	Multi-Tool Control System, Method and Medium		
K.N.	09/619,044	07/19/00	Yuan	System and Method of Exporting or Importing Object Data in a Manufacturing Execution System		
K.N.	09/637,620	08/11/00	Chi et al.	Generic Interface Builder		
K.N.	09/656,031	09/06/00	Chi et al.	Dispatching Component for Associating Manufacturing Facility Service Requestors with Service Providers		

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	Translation	
					SUB-CLASS	Yes
						No

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

K.N.	Zhou, Zhen-Hong and Rafael Reif. August 1995. "Epi-Film Thickness Measurements Using Emission Fourier Transform Infrared Spectroscopy—Part II: Real-Time <i>in Situ</i> Process Monitoring and Control." <i>IEEE Transactions on Semiconductor Manufacturing</i> , Vol. 8, No. 3.
K.N.	Telfeyan, Roland, James Moyne, Nauman Chaudhry, James Pugmire, Scott Shellman, Duane Boning, William Moyne, Arnon Hurwitz, and John Taylor. October 1995. "A Multi-Level Approach to the Control of a Chemical-Mechanical Planarization Process." Minneapolis, Minnesota: 42 nd National Symposium of the American Vacuum Society.
K.N.	Chang, E., B. Stine, T. Maung, R. Divecha, D. Boning, J. Chung, K. Chang, G. Ray, D. Bradbury, O. S. Nakagawa, S. Oh, and D. Bartelink. December 1995. "Using a Statistical Metrology Framework to Identify Systematic and Random Sources of Die- and Wafer-level ILD Thickness Variation in CMP Processes." Washington, D.C.: International Electron Devices Meeting.

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JKP:cmw

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EXAMINER'S INITIALS	PATENT APPLICATION NO.	FILING DATE	NAME	TITLE		CLASS	SUB-CLASS
K.N.	09/655,542	09/06/00	Yuan	System, Method and Medium for Defining Palettes to Transform an Application Program Interface for a Service			
	09/725,908	11/30/00	Chi et al.	Dynamic Subject Information Generation in Message Services of Distributed Object Systems			
	09/800,980	03/08/01	Hawkins et al.	Dynamic and Extensible Task Guide			
	09/811,667	03/20/01	Yuan et al.	Fault Tolerant and Automated Computer Software Workflow			
	09/927,444	08/13/01	Ward et al.	Dynamic Control of Wafer Processing Paths in Semiconductor Manufacturing Processes			
K.N.	09/928,473	08/13/01	Koh	Tool Services Layer for Providing Tool Service Functions in Conjunction with Tool Functions			
FOREIGN PATENT DOCUMENTS							Translation
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUB-CLASS		
						Yes	No
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
K.N.	Dishon, G., M. Finarov, R. Kipper, J.W. Curry, T. Schraub, D. Trojan, 4 th Stambaugh, Y. Li and J. Ben-Jacob. February 1996. "On-Line Integrated Metrology for CMP Processing." Santa Clara, California: VMIC Speciality Conferences, 1 st International CMP Planarization Conference.						
	Smith, Taber, Duane Boning, James Moyne, Arnon Hurwitz, and John Curry. June 1996. "Compensating for CMP Pad Wear Using Run by Run Feedback Control." Santa Clara, California: VLSI Multilevel Interconnect Conference.						
	Boning, Duane, William Moyne, Taber Smith, James Moyne, Roland Telfeyan, Arnon Hurwitz, Scott Shellman, and John Taylor. October 1996. "Run by Run Control of Chemical-Mechanical Polishing." <i>IEEE Trans. CPMT (C)</i> , Vol. 19, No. 4, pp. 307-314.						
K.N.	SEMI. [1986] 1996. "Standard for Definition and Measurement of Equipment Reliability, Availability, and Maintainability (RAM)." SEMI E10-96.						
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K.N.	09/928,474	08/14/01	Krishnamurthy et al.	Experiment Management System, Method and Medium		
	09/943,383	08/31/01	Shanmugasundram et al.	In Situ Sensor Based Control of Semiconductor Processing Procedure		
✓ K.N.	09/943,955	08/31/01	Shanmugasundram et al.	Feedback Control of a Chemical Mechanical Polishing Device Providing Manipulation of Removal Rate Profiles		

FOREIGN PATENT DOCUMENTS

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						Yes	No

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K.N.	Van Zant, Peter. 1997. <i>Microchip Fabrication: A Practical Guide to Semiconductor Processing</i> . Third Edition, pp. 472-478. New York, New York: McGraw-Hill.
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INFORMATION DISCLOSURE CITATION IN AN APPLICATION 				ATTY. DOCKET NO. S916/FET/FET/DV	SERIAL NO. 09/998,384	
				APPLICANT Young Joseph PAIK		
				FILING DATE November 30, 2001	GROUP 2812 2823	
U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT APPLICATION NO.	FILING DATE	NAME	TITLE	CLASS	SUB-CLASS
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INFORMATION DISCLOSURE
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APPLICATION
(PTO-1449)



ATTY. DOCKET NO.
005916
USA/FPS/MMCS/MC

SERIAL NO.
09/998,384

APPLICANT
Young Joseph PAIK

FILING DATE
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GROUP
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	5,347,446	09/13/94	Iino et al.			02/10/92
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K.N.	WO 01/33277	05/10/01	WO			X	
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		APPLICANT Young Joseph PAIK				
		FILING DATE November 30, 2001		GROUP 2842 2823		
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						Yes
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		APPLICANT Young Joseph PAIK			
		FILING DATE November 30, 2001		GROUP 2812 2823	
FOREIGN PATENT DOCUMENTS					
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS
Translation <input checked="" type="checkbox"/> Yes <input type="checkbox"/> No					
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U.S. PATENT DOCUMENTS

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						Yes	No
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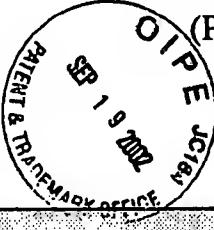
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K.N. (Signature)

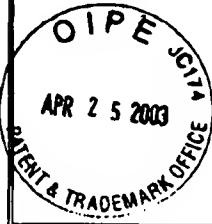
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K.N.	WO 00/79355 A1	12/28/00	WO			X
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				APPLICANT Young Joseph PAIK		
				FILING DATE November 30, 2001	GROUP 2812 2823	
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K.N.	6,455,937	09/24/02	Cunningham				03/17/99
EXAMINER <i>K.N. Cunningham</i>	DATE CONSIDERED <i>08/20/04</i>						

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U.S. PATENT DOCUMENTS							
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K.N.	6,517,413	02/11/03	Hu et al.			10/25/00	
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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Yes	No
						Yes	No
K.N.	61-66104	04/04/86	Japan			X	
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	8-23166	01/23/96	Japan			X	
	9-246547	09/19/97	Japan			X	
	WO 98/05066	02/05/98	WIPO			X	
	10-34522	02/10/98	Japan			X	
	0 869 652	10/07/98	Europe			X	
	WO 99/09371	02/25/99	WIPO			X	
	0 910 123	04/21/99	Europe			X	
	0 932 194	07/28/99	Europe			X	
↙	WO 00/00874	01/06/00	WIPO			X	
K.N.	2000-183001	06/30/00	Japan			X	
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FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
K.N.	1 071 128	01/24/01	Europe			X	
	WO 01/18623	03/15/01	WIPO			X	
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	434103	05/16/01	Taiwan			X	
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